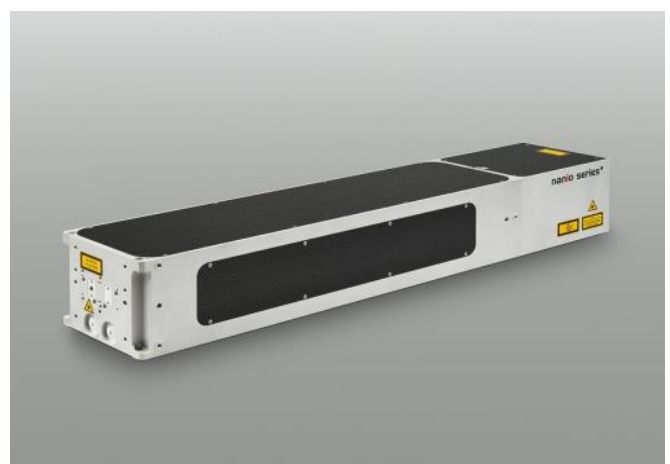
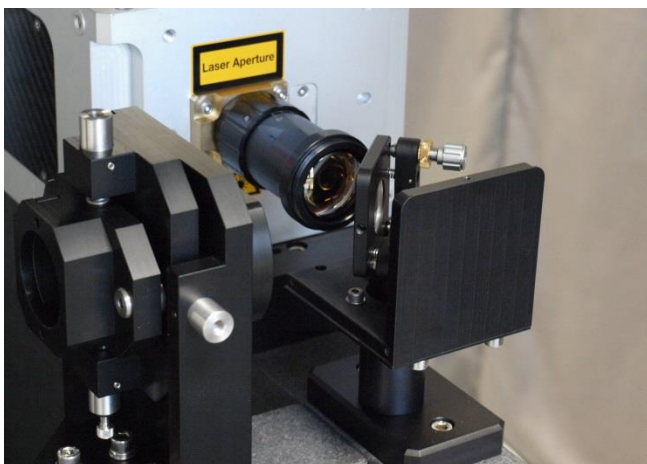




The InnoLas **Wafer Marking System IL 1000**  
for the unique Identification of your wafers



## Laser and Optics

Laser Type	Nd:YAG 355/532/1064 & CO <sub>2</sub> 10.600nm
Laser Class	Class 1 / Class 4 with open cabinet
Focus Lens	F-Theta Objective
Galvo Head	High precision digitally controlled unit
Laser Stability	±1% peak to peak

## Marking

Fonts	Dot Matrix	SEMI OCR 5x9 / 10x18 / 15x27
	Barcode	SEMI BC412, IBM BC412
	2D Code	SEMI T7
	Engraved Mode	
Checksum	SEMI / IBM / customized (optional)	
Serialization	Numeric / Alphanumeric / IBM	
Text Position	Adjustable in X-, Y-Axis and Angle	
Repeatability X and Y-direction	±75 µm (high precision) / ±100 µm (standard)	
Dot Depth	0,1 – 100µm (depending on laser & material)	
Dot Diameter	25 – 150 µm (depending on laser & material)	

## Handling System

Wafer Sizes	2 inch – 200 mm
Wafer Transfer	Single Arm Robot – Single End Effector
Wafer Alignment	Opto-mechanical
Wafer Handling	Vacuum / Edge Grip (optional)
Loading Stations	1
Throughput (wafers/hr)	100 (SEMI M13 spec. w/o reading)

## Facility Requirements

Electrical	230 V (1P/1N/1PE) / 50 Hz / 16 Amps Optional: 115-200-240-370-380-400-420-480V	
Power Consumption	1200 W	
Communication	Ethernet RJ45 (SECS/GEM optional)	
Vacuum	-800 mbar	/ 8mm OD connection
Exhaust	33,6 m <sup>3</sup> /hr	/ 50 mm ID connection
CDA – Compressed Dry Air	6 bar	/ 8mm OD connection
PFO – Process Fluid Outlet	8mm OD connection	
Cooling Water (optional)	> 5 l/min at 15°C	
Water Pressure	2-6 bar	
Weight	600 kg	
Dimension (w x l x h)	1429 x 920 x 2001 mm	

## General

System Frame	Powder coated
System Panels	Powder coated
Mini Environment	n/a
Certification	CDRH #0010530 / CE